

*At*  
Please add the following claim:

-- 29. A lithography system according to claim 3, wherein the resist coated on the substrate is chemically amplified resist. --

**R E M A R K S**

Claims 1-29 are now pending in this application.

The above amendments to the claims have been made to delete the multiple dependency of the claims and to put the application in better condition for examination. No new matter has been added.

In the event that any fees are due in connection with this paper, please charge our Deposit Account No. 01-2340.

Respectfully submitted,

ARMSTRONG, WESTERMAN, HATTORI,  
MCLELAND & NAUGHTON



Donald W. Hanson  
Attorney for Applicant  
Reg. No. 27,133

Atty. Docket No. 980511B  
Suite 1000  
1725 K Street, N. W.  
Washington, D. C. 20006  
Tel: (202) 659-2930  
Fax: (202) 887-0357  
DWH/SK/fs  
H:\HOME\fsakai\amendment\980511B-pre